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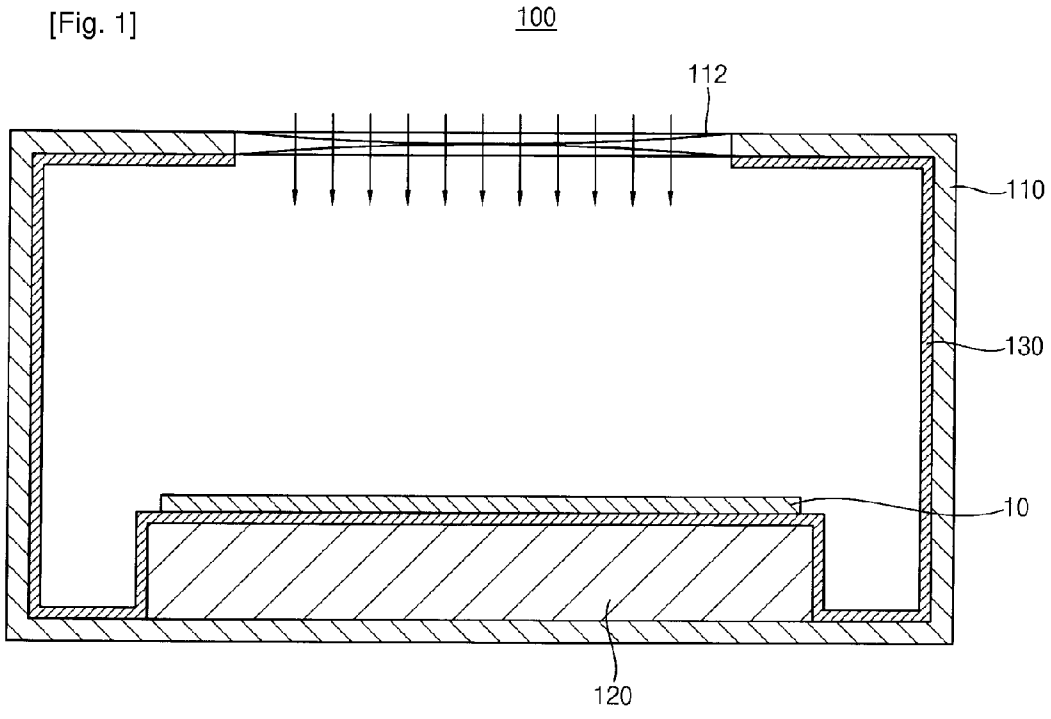
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(54) **Title:** ION IMPLANTER, INTERNAL STRUCTURE OF ION IMPLANTER AND METHOD OF FORMING A COATING LAYER IN THE ION IMPLANTER

[Fig. 1]



(57) **Abstract:** An ion implanter includes a process chamber and a coating layer. The process chamber receives a substrate and provides a space to perform an ion implantation process on the substrate. The coating layer is disposed on an inner wall of the process chamber to reduce contamination of the substrate and includes the same material as that of the substrate.

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